



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

**Yosuke SHIRATA**

Serial No.: **09/684,898**

Filed: **October 10, 2000**

For: **LITHOGRAPHY SYSTEM AND METHOD**

Group Art Unit: **2851**

Examiner: **NGUYEN, H**

Confirmation No.: **2212**

AMENDMENT

Commissioner for Patents  
Washington, D.C. 20231

Date: September 19, 2002

Sir:

In response to the Office Action dated **March 19, 2002**, the time for response of which is extended to **September 19, 2002** by a 3 month Petition for Extension of Time, please amend the above-identified application as follows:

**IN THE CLAIMS:**

Please **AMEND** the claims as follows:

1. (Twice Amended) A lithography system comprising:

an exposure apparatus which projects a pattern on to a substrate on which resist is coated,  
a substrate processing apparatus provided adjacent to said exposure apparatus which

processes the substrate:

a first chamber containing the exposure apparatus therein;

a second chamber provided adjacent to the first chamber separately from said first chamber

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